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Agency Contact:

David Moreno

Open Sky Communications

Tel: +1-415-519-3915

E-mail: dmoreno@openskypr.com

MICRON JOINS THE EBEAM INITIATIVE

SAN JOSE, Calif., February 25, 2020—The eBeam Initiative, a forum dedicated to the education and promotion of new semiconductor manufacturing approaches based on electron beam (eBeam) technologies, today announced that Micron has joined the eBeam Initiative. As an industry leader in memory and storage solutions, Micron will provide a unique and important perspective to the educational activities of the eBeam Initiative within the semiconductor photomask and lithography supply chain.

In 2009, the eBeam Initiative was launched to provide a strong voice and educational platform for eBeam technology within the photomask and semiconductor design and manufacturing community. Instrumental to its efforts, the eBeam Initiative leverages its annual [perceptions survey](#) and [mask makers' survey](#) to confirm key trends to help guide the industry forward in supporting the introduction of new eBeam technologies. With Micron – which participated in the 2019 mask makers' survey – now included among its roster of more than 50 member companies, the eBeam Initiative continues its charter to enable industry collaboration to advance the eBeam technology ecosystem.

Today, during the SPIE Advanced Lithography Conference being held at the San Jose Convention Center, the eBeam Initiative will host its 12th annual members meeting along with this year's co-sponsor, the [Center for Deep Learning in Electronics Manufacturing \(CDLe\)](#). Dr. Ezequiel Vidal-Russell, senior director of mask technology at Micron, will cover topics key to the future success of photomask manufacturing and lithography, including inverse lithography technology (ILT) and curvilinear masks for advanced memory designs. Copies of presentations will be made available after February 25 on the eBeam Initiative website at www.ebeam.org.

“eBeam technology has been instrumental in advancing the progress of the semiconductor industry – even more so today as the industry faces numerous new challenges in mask making and lithography. The support of our members is crucial to raising awareness of new developments in eBeam technology that enable the industry's success, and we sincerely appreciate their efforts,” stated Aki Fujimura, CEO of D2S, the managing company sponsor of the eBeam Initiative. “With Micron already making important contributions to our annual mask makers' survey, it gives me great pleasure to announce them as our newest member. With their expertise and unique insight, they will make an important addition to the eBeam Initiative.”

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About The eBeam Initiative

The eBeam Initiative provides a forum for educational and promotional activities regarding new semiconductor manufacturing approaches based on electron beam (eBeam) technologies. The goals of the Initiative are to reduce the barriers to adoption to enable more integrated circuit (IC) design starts and faster time-to-market while increasing the investment in eBeam technologies throughout the semiconductor ecosystem. Members, which span the semiconductor ecosystem, include: aBeam Technologies; Advantest; Alchip Technologies; AMTC; Applied Materials; Artwork Conversion; Aselta Nanographics; ASML; Cadence Design Systems; Canon; CEA-Leti; D2S; Dai Nippon Printing; EQUIcon Software GmbH Jena; eSilicon Corporation; Fraunhofer CNT; Fujitsu Semiconductor Limited; GenISys GmbH; GLOBALFOUNDRIES; Grenon Consulting; Hitachi High-Technologies; HOLON CO., LTD; HOYA Corporation; imec; IMS CHIPS; IMS Nanofabrication AG; JEOL; KIOXIA; KLA; Maglen; Mentor, a Siemens Business; Micron Technology; Multibeam Corporation; NCS; NuFlare Technology; Petersen Advanced Lithography; Photonics; Sage Design Automation; Samsung Electronics; Semiconductor Manufacturing International (Shanghai) Corporation (SMIC); STMicroelectronics; Synopsys; tau-Metrix; Tela Innovations; Tokyo Electron Ltd. (TEL); TOOL Corporation; Toppan Printing; UBC Microelectronics; Vistec Electron Beam GmbH; Xilinx and ZEISS. Membership is open to all companies and institutions throughout the electronics industry. To find out more, please visit www.ebeam.org.

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